

## Resist Compositions with Polymers having 2-Cyano Acrylic Monomer

### Abstract of the Disclosure

Acid-catalyzed positive resist compositions which are imageable with 193nm radiation and/or possibly other radiation and are developable to form  
5 resist structures of improved development characteristics and improved etch resistance are enabled by the use of resist compositions containing imaging polymer having a 2-cyano acrylic monomer.